IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1-35 (Canceled)

36. (Currently Amended) A method of manufacturing a display device comprising the steps of:

forming a thin film transistor over a substrate;

forming a pixel electrode electrically connected to the thin film transistor;

forming a film on the pixel electrode;

forming a body with a textured surface ~~on the pixel electrode~~ by a photolithography of the film; and

forming a light reflection film on the body with the textured surface.

37. (Previously presented). A method according to claim 36, wherein the pixel electrode comprises at least one of Al and Ag.

38. (Previously presented). A method according to claim 36, wherein the body with the textured surface comprises at least one material selected from the group consisting of SiO_2, MgF_2, Na_3AlF_6, an acrylic resin, and polyimide.

39. (Previously presented). A method according to claim 36, wherein the body with the textured surface has an uneven portion of 1 μm or less in height on the surface.

40. (Previously presented). A method according to claim 36, wherein the light reflection film

comprises at least one material selected from the group consisting of TiO_2, ZrO_2, Ta_2O_5, ZnS, ZnSe, ZnTe, Si, Ge, Y_2O_3, Al_2O_3, and Indium Tin Oxide.

41. (Previously presented) A method according to claim 36, wherein the display device is a reflection type liquid crystal display device.

42. (Previously presented) A method according to claim 36, wherein the display device is incorporated in at least one selected from the group consisting of a portable telephone, a video camera, a mobile computer, a head mount display, projector, a personal computer, a goggle type display, a player apparatus, and a digital camera.

43.(Currently Amended) A method of manufacturing a display device comprising the steps of:

forming a thin film transistor over a substrate;

forming a pixel electrode electrically connected to the thin film transistor~~;~~ and having a flat surface;

forming a film on the pixel electrode;

forming a body with a textured surface ~~on the pixel electrode~~ by a photolithography of the film;

forming a light reflection film on the body with the textured surface; and

flattening a surface of the light reflection film by a CMP process.

44. (Previously presented) A method according to claim 43, wherein the pixel electrode comprises at least one of Al and Ag.

45. (Previously presented) A method according to claim 43, wherein the body with the textured surface comprises at least one material selected from the group consisting of SiO_2, MgF_2, Na_3AlF_6, an acrylic resin, and polyimide.

46. (Previously presented) A method according to claim 43, wherein the body with the textured surface has an uneven portion of 1 μm or less in height on the surface.

47. (Previously presented) A method according to claim 43, wherein the light reflection film comprises at least one material selected from the group consisting of TiO_2, ZrO_2, Ta_2O_5, ZnS, ZnSe, ZnTe, Si, Ge, Y_2O_3, Al_2O_3, and Indium Tin Oxide.

48. (Previously presented) A method according to claim 43, wherein the display device is a reflection type liquid crystal display device.

49. (Previously presented) A method according to claim 43, wherein the display device is incorporated in at least one selected from the group consisting of a portable telephone, a video camera, a mobile computer, a head mount display, projector, a personal computer, a goggle type display, a player apparatus, and a digital camera.

50.(Currently Amended) A method of manufacturing a display device comprising the steps of:

forming a thin film transistor over a substrate;

forming a pixel electrode electrically connected to the thin film transistor;

forming a film on the pixel electrode;

forming a body with a textured surface ~~on the pixel electrode~~ by a photolithography of the film; and

forming a light reflection film on the body with the textured surface,

wherein the light reflection film has a higher refractive index than the body with the textured surface.

51. (Previously presented) A method according to claim 50, wherein the pixel electrode comprises at least one of Al and Ag.

52. (Previously presented) A method according to claim 50, wherein the body with the textured surface comprises at least one material selected from the group consisting of SiO_2, MgF_2, Na_3AlF_6, an acrylic resin, and polyimide.

53. (Previously presented) A method according to claim 50, wherein the body with the textured surface has an uneven portion of 1 μm or less in height on the surface.

54. (Previously presented) A method according to claim 50, wherein the light reflection film comprises at least one material selected from the group consisting of TiO_2, ZrO_2, Ta_2O_5, ZnS, ZnSe, ZnTe, Si, Ge, Y_2O_3, Al_2O_3, and Indium Tin Oxide.

55. (Previously presented) A method according to claim 50, wherein the display device is a reflection type liquid crystal display device.

56. (Previously presented) A method according to claim 50, wherein the display device is incorporated in at least one selected from the group consisting of a portable telephone, a video camera, a mobile computer, a head mount display, projector, a personal computer, a goggle type display, a player apparatus, and a digital camera.

57.(Currently Amended) A method of manufacturing a display device comprising the steps of:

forming an insulated gate field effect transistor on a semiconductor substrate;

forming a pixel electrode electrically connected to the insulated gate filed effect transistor;

forming a film on the pixel electrode;

forming a body with a textured surface ~~on the pixel electrode~~ by a photolithography of the film; and

forming a light reflection film on the body with the textured surface.

58. (Previously presented) A method according to claim 57, wherein the pixel electrode comprises at least one of Al and Ag.

59. (Previously presented) A method according to claim 57, wherein the body with the textured surface comprises at least one material selected from the group consisting of SiO_2, MgF_2, Na_3AlF_6, an acrylic resin, and polyimide.

60. (Previously presented) A method according to claim 57, wherein the body with the textured surface has an uneven portion of 1 μm or less in height on the surface.

61. (Previously presented) A method according to claim 57, wherein the light reflection film comprises at least one material selected from the group consisting of TiO_2, ZrO_2, Ta_2O_5, ZnS, ZnSe, ZnTe, Si, Ge, Y_2O_3, Al_2O_3, and Indium Tin Oxide.

62. (Previously presented) A method according to claim 57, wherein the display device is a reflection type liquid crystal display device.

63. (Previously presented) A method according to claim 57, wherein the display device is incorporated in at least one selected from the group consisting of a portable telephone, a video camera, a mobile computer, a head mount display, projector, a personal computer, a goggle type display, a player apparatus, and a digital camera.

64.(Currently Amended) A method of manufacturing a display device comprising the steps of:

forming an insulated gate field effect transistor on a semiconductor substrate;

forming a pixel electrode electrically connected to the insulated gate field effect transistor~~;~~ and having a flat surface;

forming a film on the pixel electrode;

forming a body with a textured surface ~~on the pixel electrode~~ by a photolithography of the film;

forming a light reflection film on the body with the textured surface; and

flattening a surface of the light reflection film by a CMP process.

65. (Previously presented) A method according to claim 64, wherein the pixel electrode comprises at least one of Al and Ag.

66. (Previously presented) A method according to claim 64, wherein the body with the textured surface comprises at least one material selected from the group consisting of SiO_2, MgF_2, Na_3AlF_6, an acrylic resin, and polyimide.

67. (Previously presented) A method according to claim 64, wherein the body with the textured surface has an uneven portion of 1 μm or less in height on the surface.

68. (Previously presented) A method according to claim 64, wherein the light reflection film comprises at least one material selected from the group consisting of TiO_2, ZrO_2, Ta_2O_5, ZnS, ZnSe, ZnTe, Si, Ge, Y_2O_3, Al_2O_3, and Indium Tin Oxide.

69. (Previously presented) A method according to claim 64, wherein the display device is a reflection type liquid crystal display device.

70. (Previously presented) A method according to claim 64, wherein the display device is incorporated in at least one selected from the group consisting of a portable telephone, a video camera, a mobile computer, a head mount display, projector, a personal computer, a goggle type display, a player apparatus, and a digital camera.

71.(Currently Amended) A method of manufacturing a display device comprising the steps of:

forming an insulated gate field effect transistor on a semiconductor substrate;

forming a pixel electrode electrically connected to the insulated gate field effect transistor;

forming a film on the pixel electrode;

forming a body with a textured surface ~~on the pixel electrode~~ by a photolithography of the film; and

forming a light reflection film on the body with the textured surface,

wherein the light reflection film has a higher refractive index than the body with the textured surface.

72. (Previously presented) A method according to claim 71, wherein the pixel electrode comprises at least one of Al and Ag.

73. (Previously presented) A method according to claim 71, wherein the body with the textured surface comprises at least one material selected from the group consisting of SiO_2, MgF_2, Na_3AlF_6, an acrylic resin, and polyimide.

74. (Previously presented) A method according to claim 71, wherein the body with the textured surface has an uneven portion of 1 μm or less in height on the surface.

75. (Previously presented) A method according to claim 71, wherein the light reflection film comprises at least one material selected from the group consisting of TiO_2, ZrO_2, Ta_2O_5, ZnS, ZnSe, ZnTe, Si, Ge, Y_2O_3, Al_2O_3, and Indium Tin Oxide.

76. (Previously presented) A method according to claim 71, wherein the display device is a reflection type liquid crystal display device.

77. (Previously presented) A method according to claim 71, wherein the display device is incorporated in at least one selected from the group consisting of a portable telephone, a video camera, a mobile computer, a head mount display, projector, a personal computer, a goggle type display, a player apparatus, and a digital camera.

78.(Previously Presented) A method according to claim 36, wherein the light reflection film is formed by one selected from the group consisting of a sputtering method, a coating method, and a vacuum evaporation method.

79.(Previously Presented) A method according to claim 43, wherein the light reflection film is formed by one selected from the group consisting of a sputtering method, a coating method, and a vacuum evaporation method.

80.(Previously Presented) A method according to claim 50, wherein the light reflection film is formed by one selected from the group consisting of a sputtering method, a coating method, and a vacuum evaporation method.

81.(Previously Presented) A method according to claim 57, wherein the light reflection film is formed by one selected from the group consisting of a sputtering method, a coating method, and a vacuum evaporation method.

82.(Previously Presented) A method according to claim 64, wherein the light reflection film is

formed by one selected from the group consisting of a sputtering method, a coating method, and a vacuum evaporation method.

83.(Previously Presented) A method according to claim 71, wherein the light reflection film is formed by one selected from the group consisting of a sputtering method, a coating method, and a vacuum evaporation method.

84.(New) A method according to claim 36, further comprises a step of heat treatment for leveling an uneven portion of the body with the textured surface.

85.(New) A method according to claim 43, further comprises a step of heat treatment for leveling an uneven portion of the body with the textured surface.

86.(New) A method according to claim 50, further comprises a step of heat treatment for leveling an uneven portion of the body with the textured surface.

87.(New) A method according to claim 57, further comprises a step of heat treatment for leveling an uneven portion of the body with the textured surface.

88.(New) A method according to claim 64, further comprises a step of heat treatment for leveling an uneven portion of the body with the textured surface.

89.(New) A method according to claim 71, further comprises a step of heat treatment for leveling

an uneven portion of the body with the textured surface.